

## CURRICULUM VITAE

**N. GLEZOS**

**PHYSICIST, DIRECTOR OF RESEARCH**

**INSTITUTE OF MICROELECTRONICS, NCSR "DEMOKRITOS"**

### PERSONAL

Date and place of Birth: May 1955, Athens

Family status: Married, two daughters (Myrsini, Iro)

### EDUCATION

**1973** Italian School of Athens

**1979** University of Athens , Department of Physics

**1984** University of Athens , Department of Physics, PhD in Solid State Physics

### PROFESSIONAL POSITIONS

**1979-83** PHd Student at NCSR "Demokritos"

**1985-91** Teaching Professor at the Technological Educational Institute of Pireaus

**1990-93** Research Associate (Researcher D Level) at NCSR "Demokritos", Institute of Microelectronics

**1993-94** Teaching Professor at the Technological Educational Institute of Pireaus

**1994** Researcher on contract at NCSR "Demokritos", Institute of Microelectronics

**1995-99** Researcher C Level at NCSR "Demokritos", Institute of Microelectronics

**1999-** Researcher B Level at NCSR "Demokritos", Institute of Microelectronics

**2004**

**2005-** Researcher A Level (Director of Research) at NCSR "Demokritos", Institute of Microelectronics

## RESEARCH ACTIVITIES

- Electron beam lithography
- Electron beam lithography simulation
- Molecular electronics and nanodevices
- Plastic electronics

## RECENT PROJECTS

### 1. UNI-NANO-CUPS (European Project RTN)

Duration: 2004-7

Objective : The use of cycedextrines as components of molecular devices

### 2. TASNANO (European Project NMP-STREP) Work Package Leader

Duration: 2005-2008

Objective: The construction of a parallel probing system and the use of this system for the characterization of surfaces and for molecular manipulation

## PHD THESIS SUPERVISION

1. I.Raptis, "Application of electron beam lithography to the fabrication of submicron structures", University of Athens , Solid State Physics Faculty, 1996
2. G.Patsis, "Theoretical and experimental study of electron beam lithography processing", National Technical University of Athens, 1999
3. D.Velessiotis, "Fabrication of Microelectronic micro- and nano- devices based on polyoxometallic composites", Information Faculty, University of Athens, 2006
4. G.Chaidogiannos, " Oligomeric crystals as components of organic FETs", Faculty of Electrical Engineering, Technical University of Athens, 2007
5. A.Balliou, "Memory hybrid devices based on inorganic polyoxometallates" National Technical University of Athens, in progress

## JOURNAL AND PROJECT REVIEWER

1. Various IOP Journals
2. APL, JAP
3. FET, ICT Projects

## CONFERENCE ORGANIZATION

1. MNE 2008 Conference, Organizing Committee member



## PUBLICATIONS

### International journals

1. N.M.Glezos and A.K.Theophilou, Nonzero helicity states in jellium in connection to the  $I_3^3$  group. Physica 146A, 360 (1987)
2. N.M.Glezos, Influence of the exchange effects on the plasmon excitation spectrum of metals, Physical Review B, n.43, 7538 (1991)
3. N.M.Glezos and A.G.Nassiopoulos, Lateral Resolution of Auger Electron spectroscopy in the range 5-100keV, Surface Science 254, 309 (1991)
4. E.Valamontes, A.G.Nasiopoulos, N.Glezos Backscattering and X-ray induced correction factors for AES of thin overlayers. Influence of the lateral resolution. Surf. and Interf. Anal. 16, 203 (1990)
5. E.Valamontes, A.G.Nassiopoulos and N.M.Glezos, Monte-Carlo Simulations of the point-to-point resolution in Scanning Auger Microscopy and X-ray Microanalysis of thin over-layers, Surf. and Interf. Microanalysis 19, 419 (1992)
6. N.Glezos, I.Raptis, D.Tsoukalas and M.Hatzakis, Application of a new analytical technique of electron distribution calculation to the profile simulation of a high sensitivity negative e-beam resist, J.Vac.Sci.B 10, 2606 (1992)
7. I.Raptis, N.Glezos and M.Hatzakis, Use of the Boltzmann transport equation for the evaluation of energy deposition in the case of electron sensitive resist films over composite substrates, Microelectronic Engineering 21, 289 (1993)
8. I.Raptis, N.Glezos and M.Hatzakis, Analytical evaluation of the energy deposition function in electron-beam lithography in the case of a composite substrate, J.Vac.Sci. B 11(6), 2754 (1993)
9. N.Glezos, I.Raptis, M.Hatzakis , LITHOS: A fast electron beam lithography simulator, Microelectron. Eng. 23 417(1994)
- 10.N.Glezos, I.Raptis and M.Hatzakis, LITHOS: A fast electron-beam lithography simulator-extended article, Microelectronic Engineering. 26 , 131 (1995)
11. P.Argitis, I.Raptis, C.J.Aidinis, N.Glezos, M.Bacciochi, J.Everett and M.Hatzakis, An advanced epoxy novolac resist for fast high resolution e-beam lithography, J.V.Sci.Technol. 13(6) 3030 (1995)
- 12.I.Raptis, L.Grella, P.Argitis, M.Gentilli, N.Glezos and G.Petrocco, Determination of acid diffusion and energy deposition parameters in chemically amplified resists, Microel. Eng. 30, 295 (1996)
- 13.N.Glezos and I.Raptis, A fast electron beam lithography simulator based on the Boltzmann

- transport equation, IEEE, Transactions on Computer-Aided Design of Integrated Circuits and Systems, 15(1), 92 (1996)
14. D.Tsamakis and N.Glezos, Static Current-Voltage Characteristics of Silicon n-i-n Resistors at liquid helium temperatures, Journal de Physique IV 6, C3-93 (1996)
  15. G.Kaltzas, N.Glezos, E.Valamontes and A.G.Nassiopoulos, Application of the Boltzmann transport equation in the thickness determination of thin films, Mikrochimica Acta, Suppl 13, 349, (1996)
  16. N.Glezos, G.Patsis, I.Raptis, P.Argitis, M.Gentili and L.Grella, Application of a reaction diffusion model for negative CARs in the determination of e-beam proximity correction parameters, JVST(B), 14(6), 4252 (1996)
  17. G.Patsis, I.Raptis, N.Glezos, P.Argitis, M.Hatzakis, C.J.Aidinis, M.Gentili and R.Maggiora, Gel formation theory approach for the modeling of negative chemically amplified e-beam resists, Microelectronic Engineering 35, 157 (1997)
  18. D.Tsamakis and N.Glezos, Anomalous electrical conduction in Silicon n<sup>+</sup>i n<sup>+</sup> resistors at low temperatures, Semicond. Sci.Technol. 12, 672 (1997)
  19. P.Argitis, S.Boyatzis, I.Raptis, N.Glezos and M.Hatzakis, Post exposure bake kinetics in epoxy novolac based chemically amplified resists, ACS Books, Abstracts 214:321 Symposium Series 706, Editors: H.Ito, E.Reichmanis and O.Nalamazu, 1998
  20. G.Patsis, G.Meneghini, N.Glezos and P.Argitis, Theoretical Discussion of Acid Diffusion Effects of Negative CARs based on Contrast Curve Simulation, JVST (B) 15(6), 2561 (1997)
  21. N.Glezos, G.P.Patsis, A.Rosenbusch, Z.Cui, E-beam proximity correction for negative tone chemically amplified resists taking into account post-bake effects, Microelectronic Engineering 41/42, 319 (1998)
  22. I.Raptis, N.Glezos, A.Rosenbusch, G.Patsis and P.Argitis, Calculation of energy deposition in thin resist films over multilayer substrates, Microelectronic Engineering 41/42, 171 (1998)
  23. G.Kaltsas, N.Glezos, E.Valamontes and A.G.Nassiopoulou, Thickness Determination of Thin Films based on X-ray Signal Decay Law, Surface and Interface Analysis 26, 876(1998)
  24. A.Rosenbusch, M.Ardito, Z.Cui, E. DiFabrizio, M.Gentili, N.Glezos, G.Meneghini, B.Nowotny, G.Patsis, P.Prewett, I.Raptis "Simulation of Chemically Amplified Resists in E-beam lithography", Microelectron. Eng. 46 379(1999)
  25. G.P. Patsis and N.Glezos, Molecular dynamics simulation of gel formation theory and acid diffusion in negative tone chemically amplified resists, Microel. Eng. 46, 359, (1999)
  26. G.P.Patsis, N.Glezos, I.Raptis, E.Valamontes "Simulation of roughness and free volume in chemically amplified resists using percolation theory", J. Vac. Sci. Technol. B17 3367(1999)
  27. I.Raptis, B.Nowotny, N.Glezos, M.Gentili, G.Meneghini "Electron beam lithography simulation on homogeneous and multilayer substrates", Jpn. J. Appl. Phys. 39 635 (2000)

28. P.Argitis, N.Glezos, M.Vasilopoulou, I.Raptis, M.Hatzakis, J.Everett, G.Meneghini, A.Palumbo, M.Ardito, P.Hudek, I.Kostic "Aqueous base developable epoxy resist for high sensitivity electron beam lithography", *Microelectron. Eng.* 53 453 (2000)
29. Glezos, P.Argitis, D.Velessiotis, I.Raptis, M.Hatzakis, P.Hudek, I.Kostic "Aqueous base development and acid diffusion length optimisation in negative epoxy resist for electron beam lithography", *J. Vac. Sci. Technol B*18 3431(2000)
30. P.Patsis, A.Tserepi, I.Raptis, N.Glezos, E.Gogolides, E.S.Valamontes, "Surface and line-edge roughness in wet and dry developable negative tone systems: experiment and simulation", *J. Vac. Sci. Technol B*18 3292(2000)
31. I.Raptis, N.Glezos, E.Valamontes, E.Zervas, P.Argitis "*Electron beam lithography simulation for high resolution and high density patterns*", *Vacuum* 62 263(2001)
32. X.Zianni, D.Velessiotis, N.Glezos, K.N.Trohidou, Application of the partial wave expansion method in 3-D low energy electron beam lithography simulation, *Microelectronic Engineering* 57-58 , 297 (2001)
33. N.Glezos, K.Missiakos, S.Kakabakos, P.Petrou and G.Terzoudi, Electron beam patterning of biomolecules, *Biosensors and Bioelectronics* 17 (2002) 279
34. M.Chatzychristidi, I.Raptis, C.D.Diakoumakos, N.Glezos, P.Argitis, M.Sanopoulou "Strippable aqueous base developable negative photoresist for high aspect ratio micromachining", *Microelectron. Eng.* 61-62 729(2002)
35. G. P. Patsis and N. Glezos, Probabilistic gel formation theory in negative tone chemically amplified resists used in optical and electron beam lithography, , *J. Vac. Sci. Technol. B* 20, 1303 (2002)
36. P. Patsis, N. Glezos, and E. Gogolides Monte Carlo simulation of gel formation and surface and line-edge roughness in negative tone chemically amplified resists, , *J. Vac. Sci. Technol. B* 21, 254 (2003)
37. N. Glezos, D.Velessiotis, G.Chaidogiannos, P.Argitis, D.Tsamakis, X. Zianni, Transport properties of polyoxometalate containing polymeric materials, *Synthetic Metals* , 138, 267 (2003)
38. N.Glezos, P.Argitis, D.Velessiotis and K.Diakoumakos, Tunneling transport in polyoxometalate based composite materials, *Appl. Phys. Lett.* 83 (3), 488 (2003)
39. G.Chaidogiannos, D.Velessiotis, P.Argitis, P.Koutsolelos, C.D.Diakoumakos, D.Tsamakis and N.Glezos, Tunneling and negative resistance effects for composite materials containing polyoxometalate molecules, *Microw. Eng.* 73-74, 746 (2004)
40. D.Velessiotis, N.Glezos and V.Ioannou-Sogleridis, Tungstate poloxometalates as active compound in molecular devices, *Journal of Applied Physics*, 98(8), 1-4, 2005
41. Velessiotis, D., Ioannou-Sougleridis, V., Chaidogiannos, G., & Glezos, N. (2005). Compound polymeric materials in molecular nanodevices: Electrical behavior of zero-dimension

semiconducting inorganic molecules embedded in a polymer substrate. *Journal of Physics*: 10(1), 93-96.

42. Patsis, G. P., & Glezos, N. (2005). Electron-beam lithography simulation for EUV mask applications. *Journal of Physics*: 10(1), 385-388.
43. Glezos, N., Douvas, A. M., Argitis, P., Saurenbach, F., Chrost, J., & Livitsanos, C. (2006). Electrical characterization of molecular monolayers containing tungsten polyoxometalates. *Microelectronic Engineering*, 83(4-9 SPEC. ISS.), 1757-1760
44. Patsis, G.P., Tsirikas, N., Raptis, I., Glezos, N. Electron-beam lithography simulation for the fabrication of EUV masks 2006 *Microelectronic Engineering* 83 (4-9 SPEC. ISS.), pp. 1148-1151
45. Papavassiliou, G.C.a , Anyfantis, G.C.a , Steele, B.R.b , Terzis, A.c , Raptopoulou, C.P.c , Tatakis, G.d , Chaidogiannos, G.d , Glezos, N.d , Weng, Y.e , Yoshino, H.e , Murata, Some new nickel 1,2-dichalcogenolene complexes as single-component semiconductors , K.e, *Zeitschrift fur Naturforschung - Section B Journal of Chemical Sciences* ,Volume 62, Issue 5, May 2007, Pages 679-684
46. Soluble Phthalocyanines: Perspective Materials for Electronics S. Nešpurek, G. Chaidogiannos, N. Glezos, G. Wang, S. Bořhm, J. Rakušan, M. Karásková, *Mol. Cryst. Liq. Cryst.*, Vol. 468, pp. 3–21, 2007
47. Velessiotis, D. , Maffeo, D. , Millios, C. , Makarona, E. , Viswanathan, C., Yannakopoulou, K. , Mavridis, I. , Pikramenou, Z. , Glezos, N. «Molecular nanodevices based on functionalized cyclodextrins» .(2008) *Physica Status Solidi (A) Applications and Materials*, 205 (11), pp. 2532-2535.
48. Chaidogiannos, G.a, Petraki, F., Glezos, N., Kennou, S., Nešpurek, S. «Soluble substituted phthalocyanines for OFET applications», (2008) *Materials Science and Engineering B: Solid-State Materials for Advanced Technology*, 152 (1-3), pp. 105-108.
49. Makarona, E. , Kapetanakis, E. , Velessiotis, D.M. , Douvas, A. , Argitis, P. , Normand, P. , Gotszalk, T. , Woszczyzna, M. , Glezos, N. «Vertical devices of self-assembled hybrid organic/inorganic monolayers based on tungsten polyoxometalates», (2008) *Microelectronic Engineering*, 85 (5-6), pp. 1399-1402.
50. Kapetanakis, E., Douvas, A. M., Velessiotis, D., Makarona, E., Argitis, P., Glezos, N., et al. (2008). Molecular storage elements for proton memory devices. *Advanced Materials*, 20(23), 4568-4574.
51. Douvas, A.M. , Makarona, E. , Glezos, N. , Argitis, P.a , Mielczarski, J.A. , Mielczarski, E. Polyoxometalate-based layered structures for charge transport control in molecular devices (2008) *ACS Nano*, 2 (4), pp. 733-742.
52. Šebera, J., Nešpurek, S., Kratochvílová, I., Zálíš, S., Chaidogiannos, G., & Glezos, N. (2009). Charge carrier mobility in sulphonated and non-sulphonated ni phthalocyanines: Experiment and quantum chemical calculations. *European Physical Journal B*, 72(3), 385-395.

53. Chaidogiannos, G., Petraki, F., Glezos, N., Kennou, S., & Nešpurek, S. Low voltage operating OFETs based on solution-processed metal phthalocyanines. *Applied Physics A: Materials Science and Processing*, 96(3), (2009). 763-767.
54. Kapetanakis, E., Douvas, A. M., Velessiotis, D., Makarona, E., Argitis, P., Glezos, N., et al. Hybrid organic-inorganic materials for molecular proton memory devices. *Organic Electronics: Physics, Materials, Applications*, 10(4), (2009). 711-718.
55. Woszczyzna, M., Zawierucha, P., Swiatkowski, M., Gotszalk, T., Grabiec, P., Nikolov, N., et al. Quantitative force and mass measurements using the cantilever with integrated actuator and deflection detector. *Microelectronic Engineering*, 86(4-6), (2009). 1043-1045.
56. Giacomini, M.; Pastorino, L.; Soumetz, F. Caneva; Mielczarski, J.A.; Mielczarski, E.; Rangelow I. ; Gotszalk T.; Glezos N.; Huq, Ejaz; Ruggiero C, *Data Modeling for Tools and Technologies for the Analysis and Synthesis of NANO structures : Journal of Information Technology Research*, Vol. 2, Issue 3 p 49-70 , 2009
57. Molecular junctions made of tungsten-polyoxometalate self-assembled monolayers: Towards polyoxometalate-based molecular electronics devices, D. Velessiotis, A.M. Douvas, S. Athanasiou , B. Nilsson, G. Petersson, U. Södervall, G. Alestig, P. Argitis, N. Glezos, *Microel. Eng.* ,Article in Press, doi:10.1016/j.mee.2011.01.039 (2011)
58. Lasse E. P. Kyllönen, Viswanathan Chinuswamy, Davide Maffeo, Evangelos T. Kefalas, Zoe Pikramenou, Irene M. Mavridis, Konstantina Yannakopoulou, Nikos Glezos, *Electronic transport between Au surface and STM tip via a multipodal cyclodextrin host - metallo-guest supramolecular system*, *J.Phys.Org.Chem.*, 25(3) , pp.198-206, 2012
59. Kaloudi-Chantzea, A., Karakostas, N., Pitterl, F., Raptopoulou, C.P., Glezos, N., Pistolis, G.,” Efficient supramolecular synthesis of a robust circular light-harvesting Bodipy-dye based array”, *Chemical Communications*, Volume 48, Issue 100, 28 December 2012, Pages 12213-12215
60. Velessiotis, D. , Douvas, A.M., Dimitrakis, P., Argitis, P., Glezos, N., “Conduction mechanisms in tungsten-polyoxometalate self-assembled molecular junctions” , *Microelectronic Engineering*, Volume 97, September 2012, Pages 150-153

#### **Publication in Book**

1. R. Compano, L. Molenkamp, D. J. Paul, [Technology Roadmap for Nanoelectronics](#), European Commission IST Programme: Future and Emerging Technologies, Microelectronics Advanced Research Initiative; <http://nanoworld.org/NanoLibrary/nanoroad.pdf>. chapter 4 Nanofabrication (p46-58). (1999)

#### **Publications in Books of Abstracts**

1. A.G.Nassiopoulos and N.M.Glezos, Point to point resolution in Scanning Auger Spectroscopy at high primary beam energies for surface and interface analysis, *Advance Study Institute on Surfaces and Interfaces*, 1991, Elsevier, p. 329-335



2. N.Glezos and A.G.Nassiopoulos, Scanning Auger Electron Spectroscopy with high lateral resolution in the energy range 20-100 keV. Calculation of the resolution limits, Proceedings of the 1st General Conference of the Balkan Physical Union, Thessaloniki, 1991
3. A.Rosenbusch, N.Glezos, M.Kalus and I.Raptis, SELID: a new 3D simulator for e-beam lithography, 16<sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management, SPIE Proceedings 435 (1996)
4. P.Argitis, S. Boyatzis, I. Raptis, N. Glezos, E.Tegou, E. Gogolides and M. Hatzakis, Radiation induced cationic polymerization in epoxy novolac resists : A reaction kinetics study for optimized Microlithography”, European Polymer Federation Conference, Aghia Pelagia, Crete, October 1996.
5. G.Patsis, N.Glezos, I.Raptis and P.Argitis and C.J.Aidinis “Simulation of electron beam induced gel formation in radiation sensitive polymer films” European Polymer Federation Conference, Aghia Pelagia, Crete, October 1996.
6. A.Rosenbusch, N.Glezos, M.Kalus, I.Raptis “SELID: A new 3D simulator for e-beam lithography”. 16<sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management Proc. SPIE 2884 435(1996)
7. G.Patsis, N.Glezos, I.Raptis, P.Argitis C.Aidinis “Simulation of electron beam induced gel formation in radiation sensitive polymer films”. 6<sup>th</sup> Eur. Polymer Federation Symp. of Polymeric Materials (09/1996)
8. P.Argitis, S.Boyatzis, I.Raptis, N.Glezos, E.Tegou, E.Gogolides, M.Hatzakis “Radiation induced cationic polymerization in epoxy novolac resists: A reaction kinetics study for optimized microlithography”. 6<sup>th</sup> Eur. Polymer Federation Symp. of Polymeric Materials (09/1996)
9. P.Argitis, S.Boyatzis, I.Raptis, N.Glezos, M.Hatzakis “Post exposure Bake kinetics in epoxy novolac chemically amplified resists”. ACS Symp. Polymeric Materials Science and Engineering Vol. 77 p. 471 Las Vegas (09/1997)
10. G.P.Patsis and N.Glezos, Simulation of gel formation in chemically amplified resists used in lithography, IV Int. Symposium on Polymers in Advanced technologies, Liepzig Germany, 1997
11. G.P.Patsis, N.Glezos, Simulation of gel formation in chemically amplified resists , 4<sup>th</sup> International Symposium on Polymers, Patra (Rio) , Greece 1997
12. I.Raptis, G.Meneghini, A.Rosenbusch, N.Glezos, R.Palumbo, M.Ardito, P.Argitis “Electron beam lithography on multilayer substrates: experimental and theoretical study” Proc. SPIE 3331 431(1998)

13. E.Tegou, E.Gogolides, P.Argitis, I.Raptis, N.Glezos, Z.C.H.Tan, K.Lee, P.Le, Y.Hsu and M.Hatzakis "An epoxidised novolac resist (EPR) for high resolution negative and positive tone electron beam lithography" Proc. SPIE 3339 1181(2000)
14. N.Glezos, P.Argitis, D.Velessiotis, I.Raptis, P.Hudek, I.Kostic "Process optimisation and diffusion length evaluation of a new aqueous base developable negative epoxy electron beam resist" Advanced Semiconductor Devices and Microsystems ASDAM 2000 conf. p. 231 (Slovakia, 10/2000)
15. X.Zianni, D.Velessiotis, N.Glezos and K.Trochidou, Monte Carlo calculation of the energy deposition in PPMA and oxometalate resists in low energy electron beam lithography, MMN 2000, Athens
16. I.Raptis, N.Glezos "Electron beam lithography simulation for subquartermicron and high density patterns" Proc. SISPAD 2001 p. 404
17. M. Chatzichristidi, I. Raptis, C. D. Diakoumakos, N. Glezos, P. Argitis "Strippable negative thick photoresist for micromachining applications" IUPAC Int. Symposium (IP 2001) on ionic polymerization (Greece 10/2001)
18. N. Glezos, P.Argitis, D.Velessiotis, P. Koutsolelos, C.D.Diakoumakos, A.Tserepi, and K. Beltsios. "Polyoxometalate containing polymeric materials for nanolithography and molecular devices", MRS 2002, Symposium Y, MRS Proceedings Volume 705
19. A.Vourdas, A.C.Cefalas, N.Glezos , S. Kobe and E.Sarantopoulou, AC Acharonov-Bohm phenomena in mesoscopic rings, EMRS-Spring Meeting 2002, Symposium Q, Current trends in Nanotechnologies
20. M.Biler, L.t.d. Dvorakova, S.Nespurek and N.Glezos, Poly[(ethylenedioxy)thiophene] conductive films, World Polymer Conference, 40<sup>th</sup> Symposium on Macromolecules, Paris 2004
21. D.Velessiotis , G.Chaidogiannos, N.Glezos and P.Argitis, Quantum effects in molecular nanodevices based on tungsten polyoxometalates, European Microelectronics and Packaging Symposium, Prague 2004
22. N.Glezos, Electronic transport properties of organic/inorganic composite materials in the nanoscale, Nanomeeting 2005, Minsk
23. G.C.Papavassiliou, G.C.Anyfantis, B.R.Steele, A.Terzis, C.P.Raptopoulou, G.Tatakis, G.Chaidogiannos, N.Glezos, Y.F.Weng, H.Yoshino, and K.Murata, "Single-Component Nickel-1,2-Dithiolene Complexes, Candidate Semiconductors For Field-Effect Transistors", International Conference on Science and Technology of Synthetic Metals (2006), Dublin, Ireland
24. G.Chaidogiannos, F.Petraki, N.Glezos, S.Kennou, S.Nešpůrek,"Organic transistors using metal phthalocyanines", "Soluble Phthalocyanines: Perspective Materials for Electronics" XXII Greek Solid State and Material Science Conference (2006), Patras, Greece
25. S. Nešpůrek , G. Chaidogiannos, N. Glezos, G. Wang,S. Böhm, J. Rakušan, M.

- Karásková, “ Semiconducting Soluble Phthalocyanines“, International Conference Electronic Processes in Organic Materials (ICEPOM-6) September 25 – 29, 2006, Crimea, Ukraine
26. Evaluation of sulfonated metal phthalocyanines for OTFT applications, G.Chaidogiannos, N.Glezos, K.Yannakopoulou, I.M.Mavridi, S. Kennou, F. Petraki, S. Nespurek, Rakusan, M. Karaskova, ICOE, Eindhoven, June 2007 , Oral presentation,
  27. Charging Effects in Hybrid Structures Based on Polyoxometalate Layers for Molecular Memory Applications, E. Makarona, A.M. Douvas, E.Kapetanakis, D.Velessiotis, P.Argitis, P.Normand, N.Glezos, J.Mielczarski, E. Mielczarski T.Gotszalk , M. Woszczyna, MRS Boston, November 2007, Oral presentation
  28. Soluble Substituted Phthalocyanines for OFET Applications, G. Chaidogiannos, N. Glezos, S. Nešpůrek, NN Thessaloniki, July 2007, Oral presentation
  29. Molecular Nanodevices based on Functionalized Cyclodextrins, Dimitrios Velessiotis, Davide Maffeo, Eleni Makarona, Viswanathan Chinnuswamy, Constantinos Milios, Konstantina Yannakopoulou, Irene Mavridis, Zoe Pikramenou and Nikos Glezos, MMN Athens, November 2007, Oral presentation
  30. Vertical Devices of Self-assembled Hybrid Organic/inorganic Monolayers based on Tungsten Polyoxometalates: a step towards molecular electronic devices, E.Makarona, E.Kapetanakis, D.Velessiotis, A.Douvas, P.Argitis, P. Normand, T.Gotszalk, M. Woszczyna, N.Glezos, MNE, Copenhagen, September 2007, Oral presentation
  31. Applications of water soluble metal containing phthalocyanines in organic transistors. G.Chaidogiannos, F.Petraki, N.Glezos S.Kennou and S.Nespurek, XXIII Panhellenic Conference of Solid State Physics, September 2007, Athens
  32. E. Kapetanakis, A. M. Douvas, D. Velessiotis, E. Makarona, P. Argitis, N. Glezos, P. Normand, “Molecular proton memory”, MNE 2008, Athens “Characterization of surfaces and interactions of self-assembled cyclodextrin monolayers with STM and functionalized AFM probes”,
  33. D. Maffeo, M. Woszczyna, D. Velessiotis, V. Chinnuswamy, K. Yannakopoulou, A. Paulidou, I.Mavridis, Th. Gotszalk, J. Mileczarski, E. Mileczarski, N. Glezos, , MNE 2008 Athens
  34. “Molecular proton memory”, E. Kapetanakis, A. M. Douvas, D. Velessiotis, E. Makarona, P. Argitis, N. Glezos, P. Normand, , MNE 2008, Athens
  35. Inorganic polyoxometalates as components of molecular electronic devices, P.Argitis, N.Glezos, Oral presentation, POM Workshop , NSF Meeting, Newcastle August 2010
  36. Scanning Tunnelling Spectroscopy and Topography Recovery of a Polyoxometalate-based Self-Assembled Monolayer, D. Velessiotis , S.Athanasiou, A. Douvas, P. Argitis and N. Glezos, NN Conference, Chalkidiki, July 2010
  37. Fabrication and electrical characterization of molecular nanowires based on cyclodextrin

host-guest systems, Davide Maffeo, Viswanathan Chinuswamy , Zoe Pikramenou , Irene M. Mavridis, Konstantina Yannakopoulou, Nikos Glezos, NN Conference, Chalkidiki, July 2010“

38. "On the Electrical Behavior of Planar Tungsten Polyoxometalate Self-Assembled Mono- and Bi-Layer Junctions", D. Velessiotis, A. M. Douvas, P. Dimitrakis, P. Argitis, N. Glezos, *Frontiers in Electronic Materials (FEM 2012)*, June 17 to 20, Aachen, Germany
39. "Charging Effects and Electron Transport Phenomena associated with the redox properties of self-assembled Polyoxometalate Molecules", A.Balliou, A.Douvas , D.Velessiotis, V.Ioannou-Sougleridis, P.Normand, P.Argitis, N.Glezos, *Frontiers in Electronic Materials (FEM 2012)*, June 17 to 20, Aachen, Germany
40. "Study of the transport mechanisms and charging effects in nanodevices based on inorganic polyoxometalate molecules", 38th International Conference on Micro and Nano Engineering (MNE 2012), September 16 to 20, Toulouse, France
41. "Electronic Conduction Mechanisms in Polyoxometalate Seld-Assembled Planar Molecular Junctions", D. Velessiotis, A. M. Douvas, P. Dimitrakis, P. Argitis, N. Glezos, *Materials Today Virtual Conference: Nanotechnology*, December 11-13, <http://www.materialstoday.com/virtualconference/materials-today-virtual-conference-nanotechnology>

#### **Invited Talks**

1. N.Glezos, Resolution limits of Electron Beam Lithography and the SCALPEL system, MELARI Workshop, Lille, 1999
2. N.Glezos, Electron Beam Patterning of Biomolecules, BRITE Workshop on Biosensors and Actuators, Athens, 2000
3. N. Glezos, P.Argitis, D.Velessiotis, P. Koutsolelos, C.D.Diakoumakos, A.Tserepi, and K. Beltsios. "Polyoxometalate containing polymeric materials for nanolithography and molecular devices", Symposium Y, MRS , Boston, 2002
4. N.Glezos, Electronic transport properties of organic/inorganic composite materials in the nanoscale, Nanomeeting 2005, Minsk